

| L Number | Hits | Search Text | DB | Time stamp |
|----------|---------|---|---|------------------|
| 1 | 434086 | photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:16 |
| 2 | 0 | (photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same cavity same (expos\$3 irradiat\$5) same develop\$5 same laminat\$5 same membrane | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:17 |
| 4 | 151747 | (cover membrane) near2 (layer film coating) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:27 |
| 5 | 13 | (photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same (cavity channel microchannel micro-channel well microwell micro-well chamber) same laminat\$5 same membrane | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:21 |
| 6 | 4909745 | (cavity channel microchannel micro-channel well microwell micro-well chamber) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:22 |
| 7 | 7959 | ((laminat\$5 cover\$3) with ((cover membrane) near2 (layer film coating)) with ((cavity channel microchannel micro-channel well microwell micro-well chamber)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:27 |
| 8 | 345 | (photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same ((laminat\$5 cover\$3) with ((cover membrane) near2 (layer film coating)) with ((cavity channel microchannel micro-channel well microwell micro-well chamber))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:24 |
| 9 | 35 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same ((laminat\$5 cover\$3) with ((cover membrane) near2 (layer film coating)) with ((cavity channel microchannel micro-channel well microwell micro-well chamber)))) and (430/\$.ccls. 264/\$.ccls. 204/\$.ccls. 205/\$.ccls.) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:24 |
| 10 | 4826 | ((laminat\$5 cover\$3) with membrane with ((cavity channel microchannel micro-channel well microwell micro-well chamber))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:28 |
| 11 | 1810 | (microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:28 |
| 12 | 46 | ((laminat\$5 cover\$3) with membrane with ((cavity channel microchannel micro-channel well microwell micro-well chamber))) and ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:30 |
| 15 | 21 | (photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same ((laminat\$5 cover\$3) with membrane with ((cavity channel microchannel micro-channel well microwell micro-well chamber))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:33 |
| 16 | 9468 | (photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first! | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:33 |

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| 17 | 8493 | (photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second! | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:33 |
| 19 | 35491 | photomask photo-mask photo adj mask | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:34 |
| 22 | 30876 | (electrode gate opaque shield\$3) near2 mask | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:36 |
| 23 | 10 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) same ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) same (photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:37 |
| 24 | 270 | (photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same (photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:37 |
| 25 | 59 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same (photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask)) same ((cavity channel microchannel micro-channel well microwell micro-well chamber)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:41 |
| 26 | 699 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) with ((cavity channel microchannel micro-channel well microwell micro-well chamber)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:41 |
| 27 | 741 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) with ((cavity channel microchannel micro-channel well microwell micro-well chamber)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:41 |
| 28 | 18764 | (electrochemical electro-chemical electro adj chemical) adj cell | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:41 |
| 29 | 0 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) with ((cavity channel microchannel micro-channel well microwell micro-well chamber))) same ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) with ((cavity channel microchannel micro-channel well microwell micro-well chamber))) same (photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:42 |

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| 31 | 37 | ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) ((electrochemical electro-chemical electro adj chemical) adj cell)) and ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) and ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) and ((cavity channel microchannel micro-channel well microwell micro-well chamber)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:45 |
| 32 | 86 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:45 |
| 33 | 126 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:46 |
| 34 | 0 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)) with (((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask)) with (single near4 (expos\$3 irradiat\$5)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:46 |
| 35 | 0 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)) same (((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask)) same (single near4 (expos\$3 irradiat\$5)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:48 |
| 36 | 0 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)) same (((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask)) same (one near4 (expos\$3 irradiat\$5)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:47 |
| 37 | 0 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)) same (((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:47 |
| 38 | 10 | ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) same (photomask photo-mask photo adj mask) same ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) same ((electrode gate opaque shield\$3) near2 mask) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:47 |

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| 39 | 124196 | (single one)near4 (expos\$3 irradiat\$5) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:49 |
| 40 | 12 | (photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask) same ((single one)near4 (expos\$3 irradiat\$5)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:53 |
| 41 | 40 | (photomask photo-mask photo adj mask) with cover\$3 with ((electrode gate opaque shield\$3) near2 mask) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:51 |
| 42 | 710 | (back-side backside back adj side) adj (expos\$3 irradiat\$5) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:52 |
| 43 | 734 | (photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:53 |
| 44 | 5 | ((photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask)) same ((back-side backside back adj side) adj (expos\$3 irradiat\$5)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:54 |
| 46 | 1 | ((back-side backside back adj side) adj (expos\$3 irradiat\$5)) and 430/395.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:54 |
| - | 60 | MADOU-M-.in. MADOU-MARC-.in. MADOU-MARC-J-.in. MADOU-MARK-J-.in. MADOU-M-J-.in. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 15:33 |
| - | 711108 | resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:54 |
| - | 11 | (MADOU-M-.in. MADOU-MARC-.in. MADOU-MARC-J-.in. MADOU-MARK-J-.in. MADOU-M-J-.in.) and (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 15:45 |
| - | 1810 | (microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:28 |
| - | 4 | ((("4874500") or ("4900405"))).PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 15:46 |
| - | 421 | (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) and ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 15:48 |
| - | 34233 | (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with negative | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 15:48 |
| - | 75 | ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) and ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with negative) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 15:49 |
| - | 96841 | electrochemical electro-chemical electro adj chemical | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 15:52 |

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| - | 0 | ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with negative) same (cavity chamber)) same ((laminat\$5) with membrane) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:07 |
| - | 1153 | liga! | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 15:54 |
| - | 105 | ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) and liga! | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 15:59 |
| - | 68 | liga! and 430/\$.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:09 |
| - | 4964576 | channel microchannel micro-channel cavity chamber void well | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:28 |
| - | 59543 | (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel microchannel micro-channel cavity chamber void well) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:33 |
| - | 21 | ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel microchannel micro-channel cavity chamber void well)) with cover\$3 with membrane | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:33 |
| - | 202 | ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel microchannel micro-channel cavity chamber void well)) and ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:35 |
| - | 5499 | (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel microchannel micro-channel cavity chamber void well) with (cover\$3 membrane laminat\$5) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:34 |
| - | 36 | ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel microchannel micro-channel cavity chamber void well) with (cover\$3 membrane laminat\$5)) and ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:42 |
| - | 309 | ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) with (method process step) with (form\$3 formation manufactur\$3 produc\$5) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:45 |
| - | 1 | ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) with (method process step) with (form\$3 formation manufactur\$3 produc\$5)) same ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with negative) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:44 |
| - | 15 | ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) with (method process step) with (form\$3 formation manufactur\$3 produc\$5)) same (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:47 |

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| - | 4966878 | (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same membrane (channel microchannel micro-channel cavity chamber void well) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:53 |
| - | 1160 | (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same membrane same (channel microchannel micro-channel cavity chamber void well) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 16:55 |
| - | 86 | ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same membrane same (channel microchannel micro-channel cavity chamber void well)) and 430/\$.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:08 |
| - | 25540 | (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first! | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:08 |
| - | 20915 | (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second! | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:09 |
| - | 3150 | (back-side back adj side backside) near2 (expos\$3 irradiat\$5) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:11 |
| - | 4 | ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first!) same ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second!) same ((back-side back adj side backside) near2 (expos\$3 irradiat\$5)) same electrode ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first!) same ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second!) same ((back-side back adj side backside) near2 (expos\$3 irradiat\$5)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:12 |
| - | 18 | (electrochemical electro-chemical electro adj chemical) near cell | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:15 |
| - | 19879 | ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) ((electrochemical electro-chemical electro adj chemical) near cell) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:16 |
| - | 21676 | photomask photo-mask photo adj mask | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:48 |
| - | 35491 | (membrane cover) near (layer film) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:19 |
| - | 79461 | | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:20 |

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| - | 0 | ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) ((electrochemical electro-chemical electro adj chemical) near cell)) and ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (photomask photo-mask photo adj mask) same ((membrane cover) near (layer film)) same (channel microchannel micro-channel cavity chamber void well)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:22 |
| - | 8 | ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (photomask photo-mask photo adj mask) same ((membrane cover) near (layer film)) same (channel microchannel micro-channel cavity chamber void well)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:24 |
| - | 29 | ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) ((electrochemical electro-chemical electro adj chemical) near cell)) and ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) and (photomask photo-mask photo adj mask) and ((membrane cover) near (layer film)) and (channel microchannel micro-channel cavity chamber void well)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:26 |
| - | 28590 | (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (develop\$5 etch\$4 form\$3) with (channel microchannel micro-channel cavity chamber void well) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:51 |
| - | 50 | ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (develop\$5 etch\$4 form\$3) with (channel microchannel micro-channel cavity chamber void well)) same (fluid near2 communication) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:54 |
| - | 434086 | photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 17:54 |
| - | 392389 | (channel microchannel micro-channel cavity chamber void well) near2 (two large\$1 small\$2 big\$4) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:02 |
| - | 29 | ((channel microchannel micro-channel cavity chamber void well) near2 (two large\$1 small\$2 big\$4)) same ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first!) same ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second!) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/09 18:03 |